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IN THE SPECIFICATION

Plesse replace paragraph 48 with the following rewritten paragraph:

As another example, U.S. Patent Application Numbers 10/398,652 filed April 14, 2003 and pending (The '652 Application), and 10/168,544 filed July 2, 2002 and issued May 10, 2005 as U.S. Patent No. 6,891,124 (The '544 Application) disclose a system in which infrared spectroscopy is used to detect the temperature of the silicon wafer undergoing processing. Such a system can be advantageously combined with the system of the present invention using the same infrared radiation source. One or more of the detectors of the present invention may be modified to measure transmission or reflection spectra, from which consumable part temperature can be determined, in the same way as wafer temperature in the '652 and '544 applications. The entire content of each of the '652 and '544 applications is incorporated herein by reference.